

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	8	(substrate or wafer or semiconductor) and "134".clas. and splash\$7 and (rotat\$4 or spin\$4) with (rough\$3 or web\$4 or mesh\$4 or filtrate or filtrat\$5 or screen)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/09/30 22:32
L2	8	(substrate or wafer or semiconductor) and "134".clas. and splash\$7 and (rotat\$4 or spin\$4) with (rough\$3 or web\$4 or mesh\$4 or filtrate or filtrat\$5 or screen)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/30 22:34
L3	321	(substrate or wafer or semiconductor) and splash\$7 and (rotat\$4 or spin\$4) with (rough\$3 or web\$4 or mesh\$4 or filtrate or filtrat\$5 or screen)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/30 22:34
L4	880	(substrate or wafer or semiconductor) and (bounc\$5 or splash\$7 or rebound\$5) and (rotat\$4 or spin\$4) with (rough\$3 or web\$4 or mesh\$4 or filtrate or filtrat\$5 or screen)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/30 22:35
L5	51	(substrate or wafer) and "134".clas. and ((splash\$3 or spatter\$3 or splatter\$3) with (guard\$3 or catch\$3 or protect\$3 or baffle or cup)) and (rotat\$4 or spin\$4) and (sponge or web or roughened or adhere\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/30 22:35
L6	68	(substrate or wafer or semiconductor) and (bounc\$5 or splash\$7 or rebound\$5 or spatter\$3 or splatter\$3) and (rotat\$4 or spin\$4) with (sponge or web or roughened or adhere\$3 or rough\$3 or web\$4 or mesh\$4 or filtrate or filtrat\$5 or screen) with (guard\$3 or catch\$3 or protect\$3 or baffle or cup)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/30 22:37

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L7	672	(substrate or wafer or semiconductor) and (bounc\$5 or splash\$7 or rebound\$5 or spatter\$3 or splatter\$3) and (rotat\$4 or spin\$4) and (sponge or web or roughened or adhere\$3 or rough\$3 or web\$4 or mesh\$4 or filtrate or filtrat\$5 or screen) with (guard\$3 or catch\$3 or protect\$3 or baffle or cup)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/30 22:37
L8	87	(substrate or wafer or semiconductor) and (rotat\$4 or spin\$4) and (sponge or web or roughened or adhere\$3 or rough\$3 or web\$4 or mesh\$4 or filtrate or filtrat\$5 or screen) with (guard\$3 or catch\$3 or protect\$3 or baffle or cup) with (bounc\$5 or splash\$7 or rebound\$5 or spatter\$3 or splatter\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/30 22:41
L9	255	(substrate or wafer or semiconductor) and (rotat\$4 or spin\$4) and (splash near2 guard)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/30 22:39
L10	46	(substrate or wafer or semiconductor) and (rotat\$4 or spin\$4) and (sponge or web or mesh\$4 or screen) with (guard\$3 or catch\$3 or protect\$3 or baffle or cup) with (bounc\$5 or splash\$7 or rebound\$5 or spatter\$3 or splatter\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/30 22:41